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1. (Twice Amended) An embedded electroconductive layer comprising:  
any one of an opening part or a depressed part formed in an insulating  
film on a substrate;  
a barrier layer covering said opening part or said depressed part;  
a metal growth promoting layer on said barrier layer, said metal growth  
promoting layer being made of a material different from that of said barrier layer; and  
an electroconductive layer embedded in said opening part or said  
depressed part via said barrier layer and said metal growth promoting layer.

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5. (Twice Amended) An embedded electroconductive layer comprising:  
any one of an opening part or a depressed part formed in an insulating  
layer on a substrate;  
a ground layer containing oxygen at a high concentration in the lower  
part thereof and at a low concentration in the upper part thereof, and said ground layer  
covering the surface of said insulating film in said opening part or said depressed part; and  
an electroconductive layer embedded in said opening part or said depressed part via said  
ground layer.